

WHAT IS CLAIMED IS:

1. A plasma CVD apparatus comprising:
 - a vacuum chamber;
 - an introducing means for introducing a gas into the vacuum chamber;
 - 5 an exhaust means for exhausting the gas from the vacuum chamber to an outside;
 - an electrode for supplying an electric energy inside the vacuum chamber;
 - a supporting means for supporting a substrate opposing the electrode,
 - wherein an introducing port is located adjacent to an electrode side surface of
 - 10 the substrate,
 - wherein a plurality of openings are located on a surface of the electrode opposing the substrate,
 - wherein the gas is exhausted from the plurality of openings to the outside of the vacuum chamber.
- 15 2. An apparatus according to claim 1, further comprising:
 - a transporting means for transporting continuously a flexible substrate.
3. An apparatus according to claim 1,
 - wherein each of the plurality of openings is circular,
 - wherein the plurality of openings are located on the surface of the electrode
- 20 at constant intervals.
4. An apparatus according to claim 1, wherein the electrode is a mesh-like plate.
5. A discharge electrode comprising:

two electrodes opposing each other,
wherein a plurality of openings are located on a surface of one of the two
electrodes,
wherein a gas is exhausted from the plurality of openings.